

## Supporting information to

# Tangled effects of CuCl precursor and Zn, Sn promoters used for the methylchlorosilanes direct synthesis

L. Riviere<sup>1</sup>, E. Blaser<sup>2</sup>, C. Rosier<sup>2</sup>, M. Huet<sup>2</sup>, C. Geantet<sup>1</sup> and S. Loridant<sup>1,\*</sup>

<sup>1</sup> Université Claude Bernard Lyon 1, CNRS, IRCELYON, UMR 5256, Villeurbanne, F-69100, France

<sup>2</sup> R&D Laboratory, Elkem Silicones France, 69190 Saint Fons, France

\*stephane.loridant@ircelyon.univ-lyon1.fr

## Thermodynamic calculations

Standard enthalpy of formation at 583 K:

$$\Delta_f H(583 \text{ K}) = \Delta_f H(298 \text{ K}) + C_p \times (583 - 298)$$

with  $\Delta_f H(298 \text{ K})$  the standard enthalpy of formation at 298 K,  $C_p$  the heat capacity.

Standard entropy of formation at 583 K:

$$\Delta S^\circ(583 \text{ K}) = \Delta S^\circ(298 \text{ K}) + C_p \times \ln\left(\frac{583}{298}\right)$$

with  $\Delta S^\circ(298 \text{ K})$  the standard entropy of formation at 298 K.

**Table S1.** Heat capacities, standard enthalpies and standard entropies of formation of different compounds.

Compound	$C_p$ (600 K) (kJ.mol <sup>-1</sup> .K <sup>-1</sup> )	Ref.	$\Delta_f H$ (583 K) (kJ.mol <sup>-1</sup> )	$\Delta_f H$ (298 K) (kJ.mol <sup>-1</sup> )	Ref.	$\Delta S^\circ$ (583 K) (kJ.mol <sup>-1</sup> .K <sup>-1</sup> )	$\Delta S^\circ$ (298 K) (kJ.mol <sup>-1</sup> .K <sup>-1</sup> )	Ref.
Si (s)	0.0200	S1	0	0	S1	0.032	0.019	S1
Cu (s)	0.0244	S1	0	0	S1	0.050	0.033	S1
CuCl (s)	0.0485	S1	-123.4	-137.2	S1	0.118	0.086	S1
SiCl <sub>4</sub> (g)	0.1020	S2	-632.9	-662.2	S2	0.399	0.331	S2
Cu <sub>3</sub> Si (s) <sup>a</sup>	0.0233	S3	-7.0	-13.6	S4	0.023	0.007	S5
Cu <sub>3.75</sub> Si (s) <sup>a,b</sup>	0.0235	S3	-4.4	-11.1	S6	0.022	0.007	S5
Cu <sub>5</sub> Si (s) <sup>a</sup>	0.0237	S3	-3.8	-10.5	S4	0.021	0.006	S5

<sup>a</sup>: the calculation of heat capacities of copper-silicon silicide was performed by using the

Neumann-Kopp rule: 
$$C_p(Cu_xSi_y) = \frac{x \times C_p(Cu) + y \times C_p(Si)}{x + y}$$

<sup>b</sup>: Cu<sub>3.75</sub>Si corresponds to Cu<sub>15</sub>Si<sub>4</sub>.

Standard enthalpy of reaction:

$$\Delta_r H^\circ(583 \text{ K}) = \sum (v_p \times \Delta_f H^\circ(583 \text{ K})_p) - \sum (v_r \times \Delta_f H^\circ(583 \text{ K})_r)$$

with  $v_p$  and  $v_r$  the stoichiometric coefficients of products and reactants, respectively.

Standard entropy of reaction:

$$\Delta_r S^\circ(583 \text{ K}) = \sum (v_p \times S^\circ(583 \text{ K})_p) - \sum (v_r \times S^\circ(583 \text{ K})_r)$$

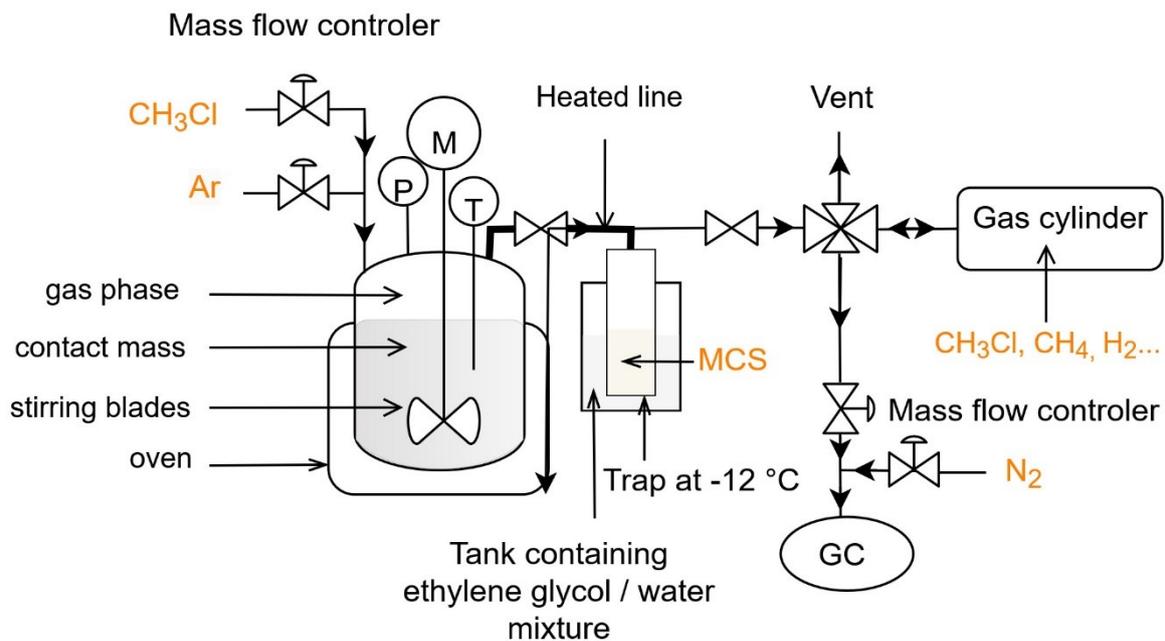
Gibbs free energy:

$$\Delta_r G^\circ(583 \text{ K}) = \Delta_r H^\circ(583 \text{ K}) - 583 \times \Delta_r S^\circ(583 \text{ K})$$

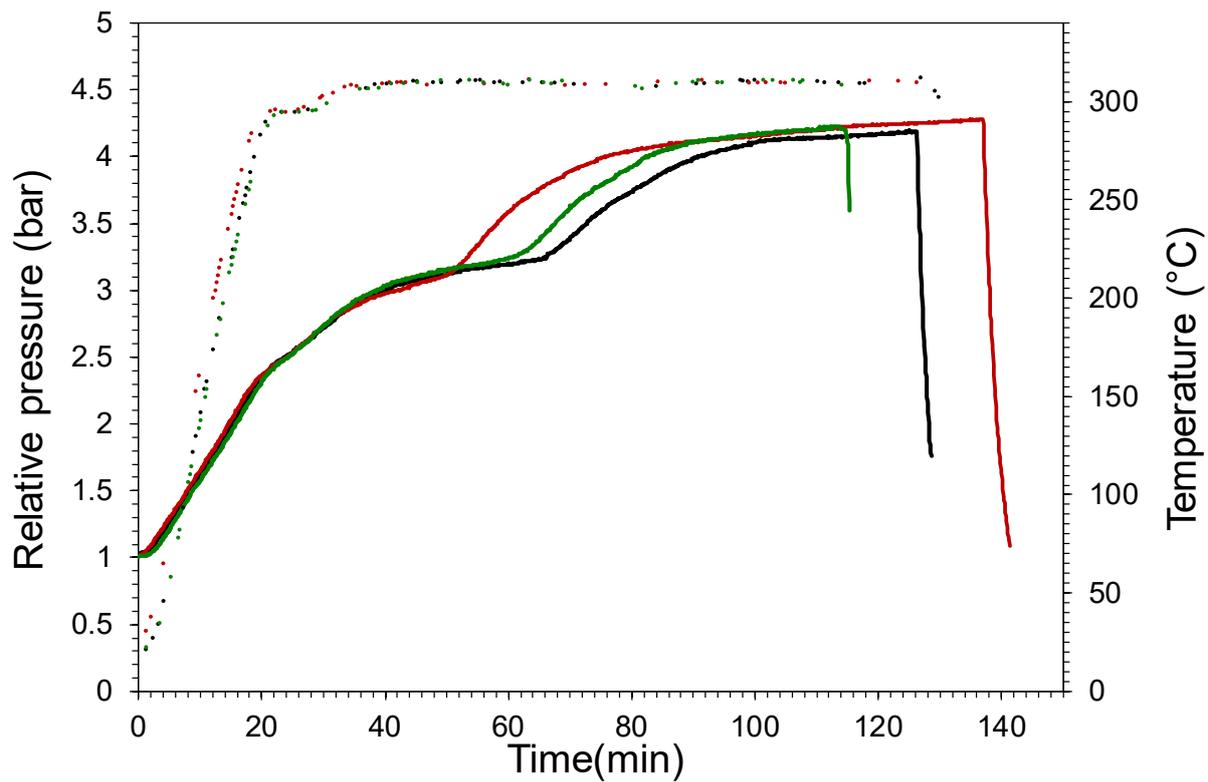


**Table S2.** Standard enthalpies and entropies of reaction and Gibbs free energies of different compounds.

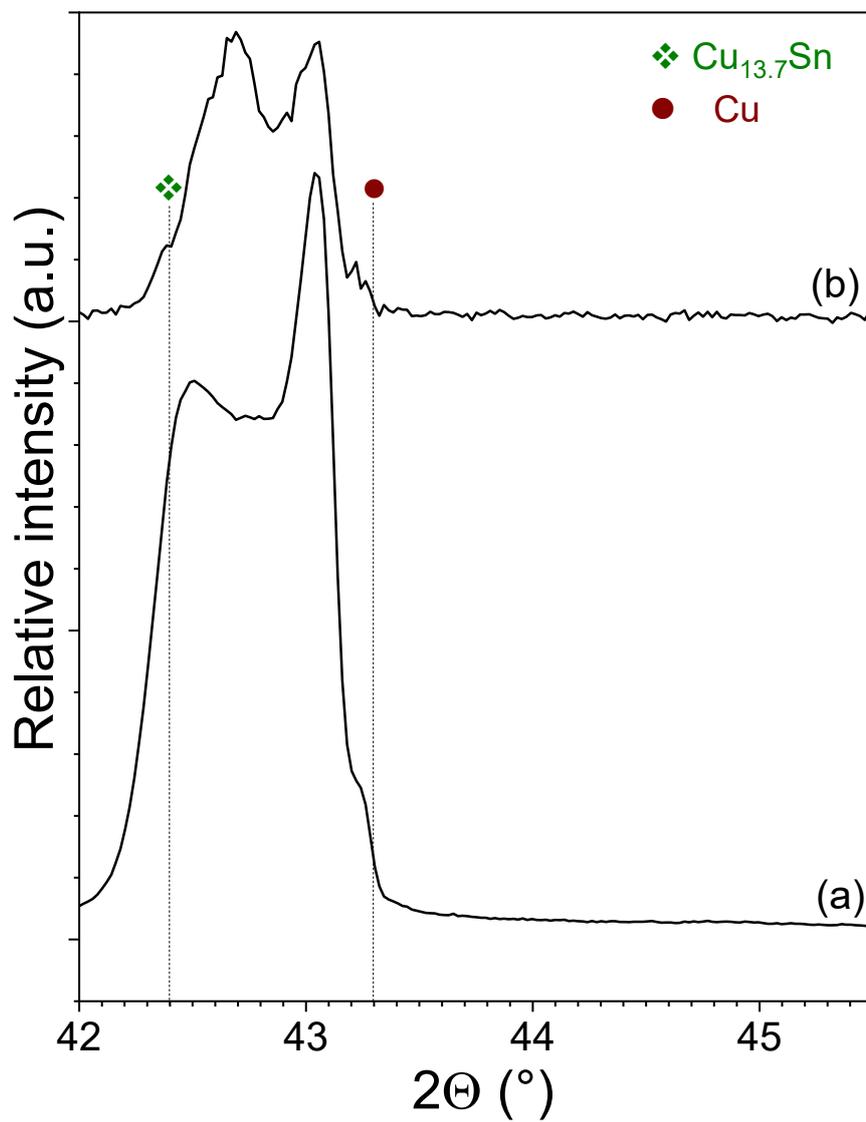
<b>Reaction</b>	$\Delta_r H^\circ(583\text{ K})$ <b>(kJ.mol<sup>-1</sup>)</b>	$\Delta_r S^\circ(583\text{ K})$ <b>(kJ.mol<sup>-1</sup> K<sup>-1</sup>)</b>	$\Delta_r G^\circ(583\text{ K})$ <b>(kJ.mol<sup>-1</sup>)</b>
$4\text{ CuCl}_{(s)} + \text{Si}_{(s)} \rightarrow 4\text{ Cu}_{(s)} + \text{SiCl}_{4(g)}$	-139.4	0.089	-191.6
$20\text{ CuCl}_{(s)} + 9\text{ Si}_{(s)} \rightarrow 4\text{ Cu}_5\text{Si}_{(s)} + 5\text{ SiCl}_{4(g)}$	-711.8	-0.584	-370.8
$15\text{ CuCl}_{(s)} + 7.75\text{ Si}_{(s)} \rightarrow 4\text{ Cu}_{3.75}\text{Si}_{(s)} + 3.75\text{ SiCl}_{4(g)}$	-540.3	-0.446	-280.4
$12\text{ CuCl}_{(s)} + 7\text{ Si}_{(s)} \rightarrow 4\text{ Cu}_3\text{Si}_{(s)} + 3\text{ SiCl}_{4(g)}$	-445.9	-0.362	-234.9



**Figure S1.** Experimental apparatus for catalytic testing in stirred batch reactor.



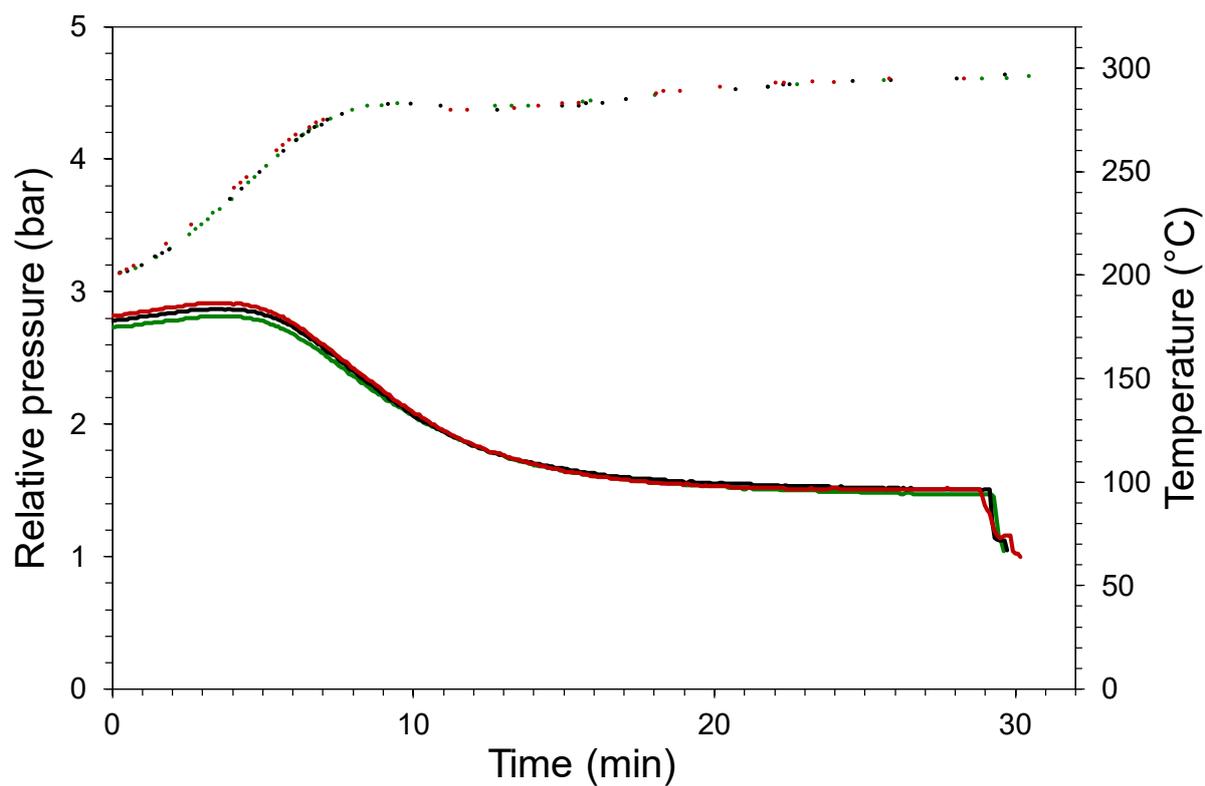
**Figure S2.** Evolutions of temperature and relative pressure with time of PM-Zn<sub>0.30</sub> contact mass during pretreatment at 310 °C for 2 h. The temperature curves are plotted as dashed lines.



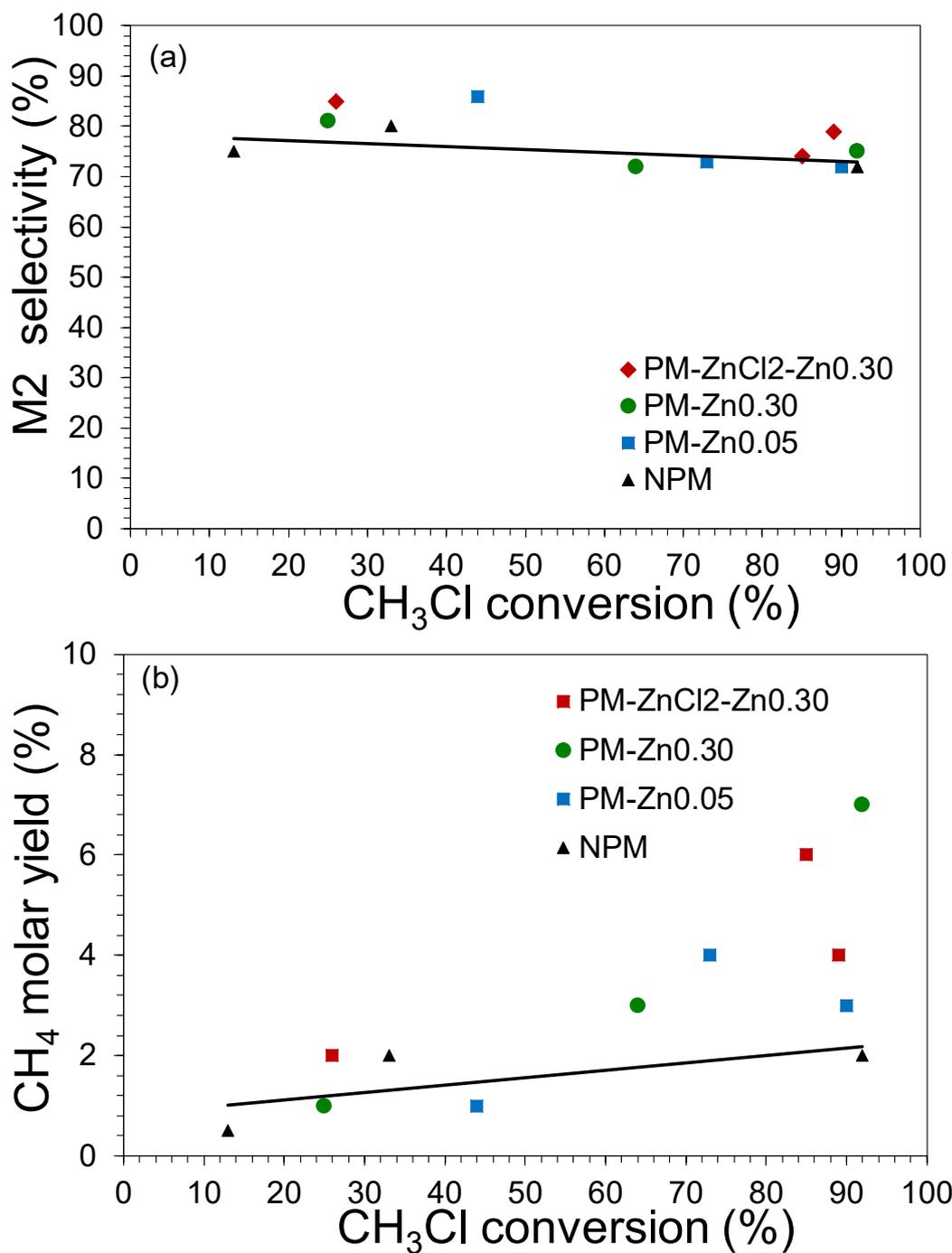
**Figure S3.** XRD diffractograms in the  $2\theta$  angle range of  $42\text{-}46^\circ$  of  $\text{Cu}_{0.9}\text{Sn}_{0.1}$  (a) before and (b) after pretreatment at  $310^\circ\text{C}$ .  $\text{Cu}_{0.9}\text{Sn}_{0.1}$  was a mixture of two bronzes.  $\text{Cu}_{13.7}\text{Sn}$  and  $\text{Cu}$  cubic phases were indexed with the PDF 65-6821 and PDF 04-0836 patterns, respectively.

**Table S3.** Catalytic performance obtained for three tests with PM-Zn0.30 contact mass pretreated at 310 °C for 30 min.

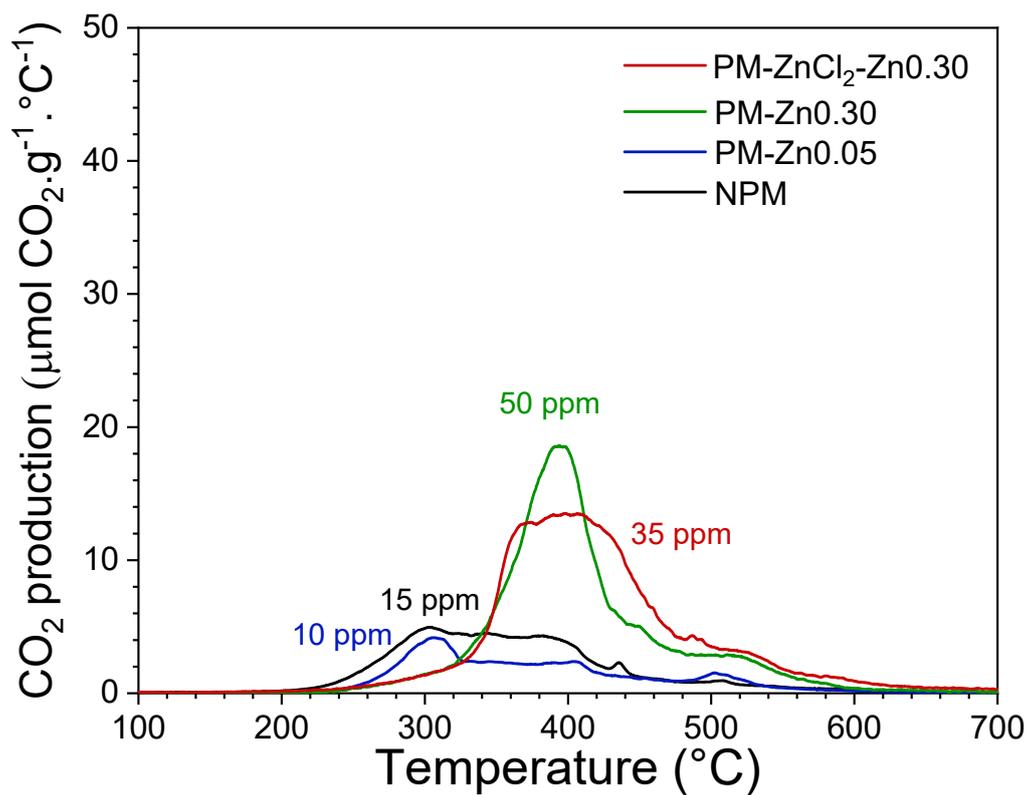
	<b>X(CH<sub>3</sub>Cl)</b> <b>(%)</b>	<b>Si selectivity (%)</b>			
		<b>M2</b>	<b>M1</b>	<b>M3</b>	<b>MH</b>
	90	73	19	3	0.8
	92	76	15	4	1.9
	95	76	15	2	0.9
<b>Average (%)</b>	92	75	16	3	1.2
<b>Standard deviation (%)</b>	2	2	2	1	0.7



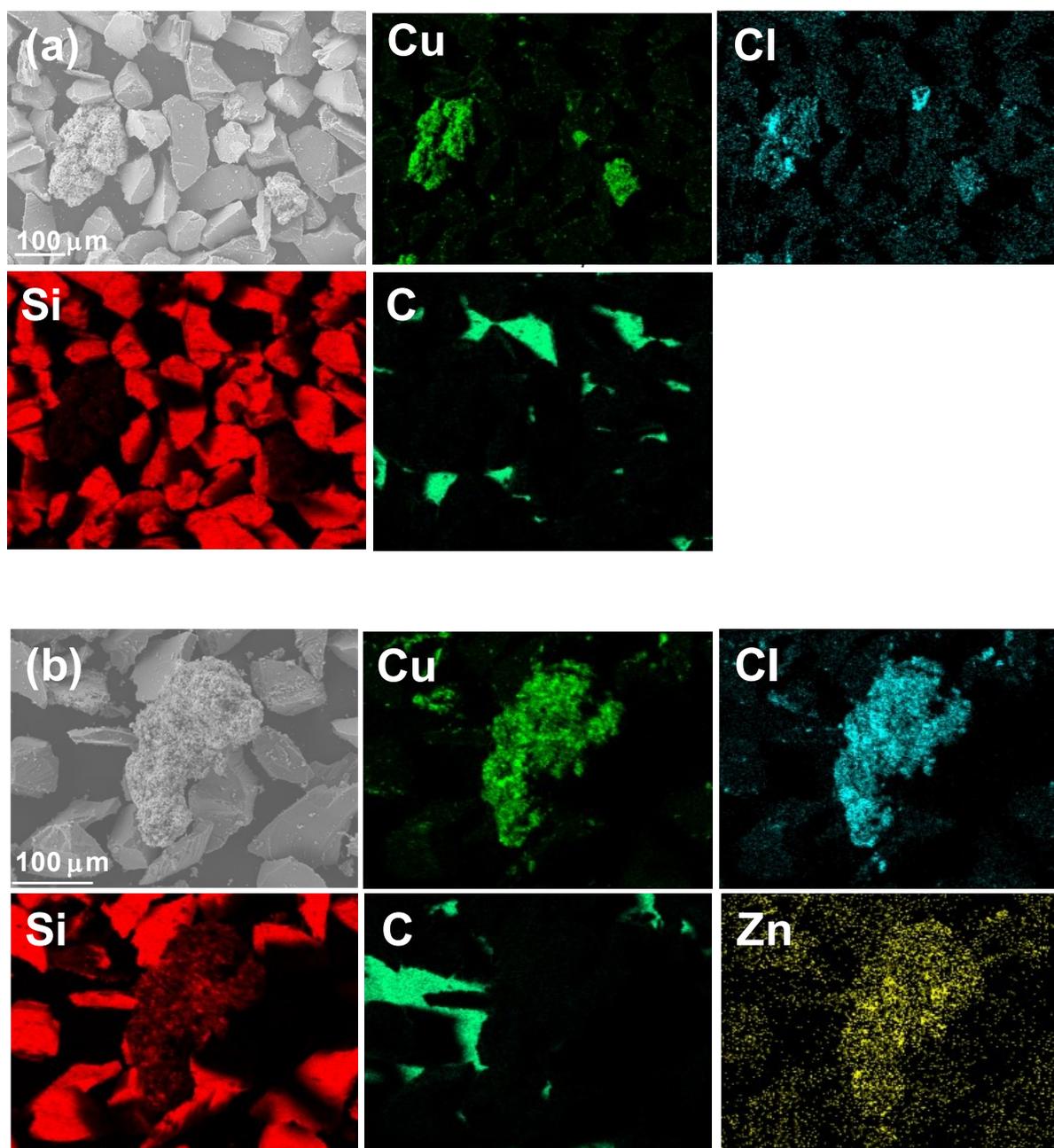
**Figure S4.** Evolutions of temperature and relative pressure with time of PM-Zn<sub>0.30</sub> mass during reaction. The temperature curves rising from 200 to 295 °C are plotted as dashed lines.



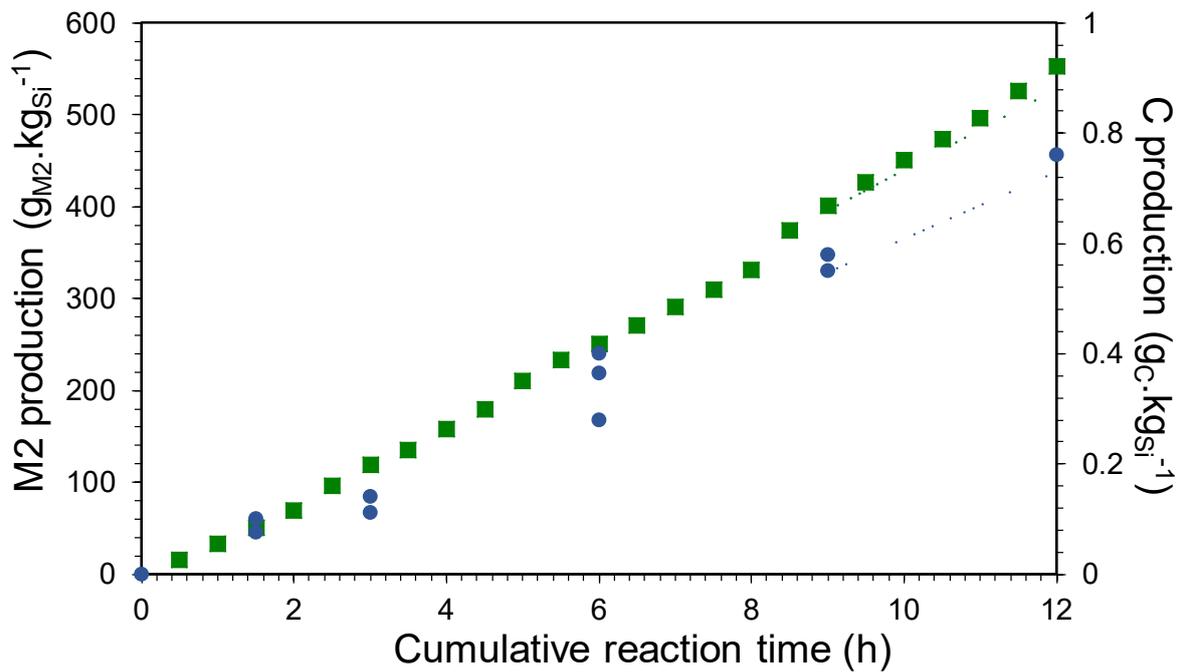
**Figure S5.** Evolution of the (a) M2 selectivity and (b) CH<sub>4</sub> molar yield with the CH<sub>3</sub>Cl conversion at 295 °C for different contact masses.



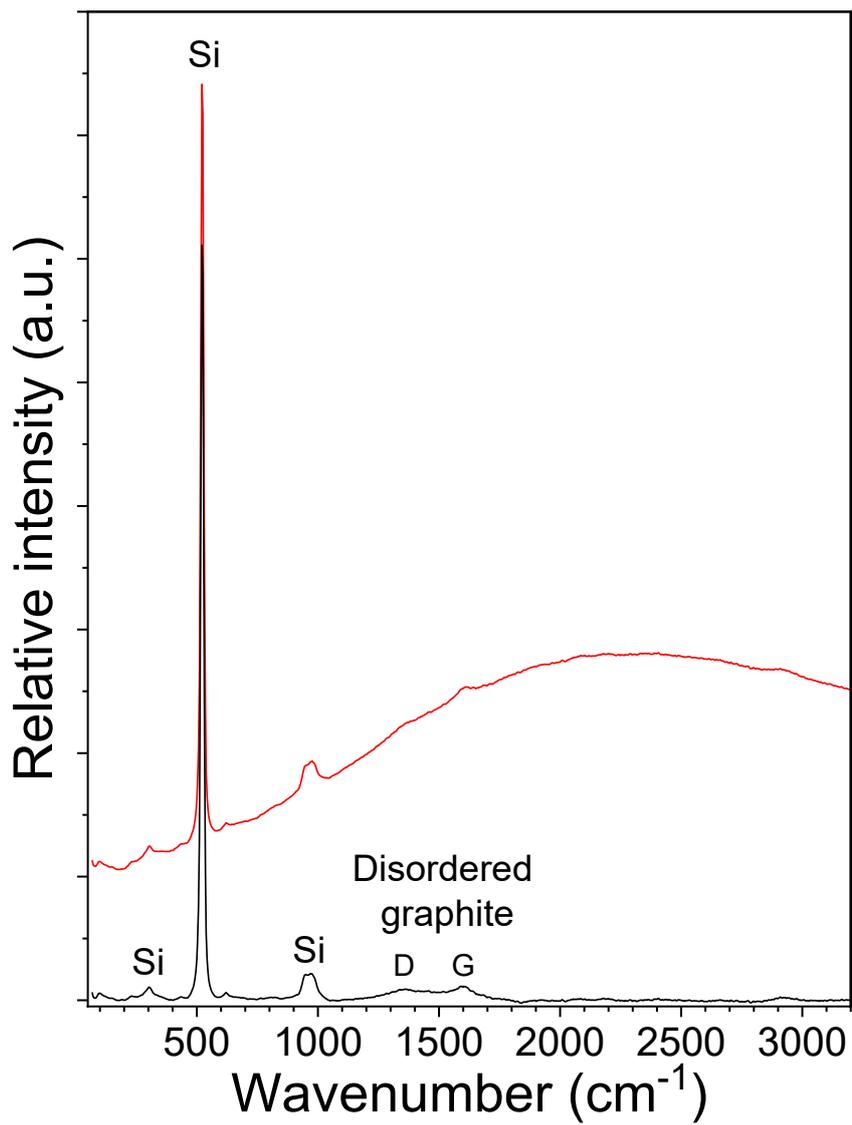
**Figure S6.** TPO curves of different contact masses after reaction at 295  $^\circ\text{C}$  (89-92% of CH<sub>3</sub>Cl conversion, 0.5-0.6% of Si conversion).



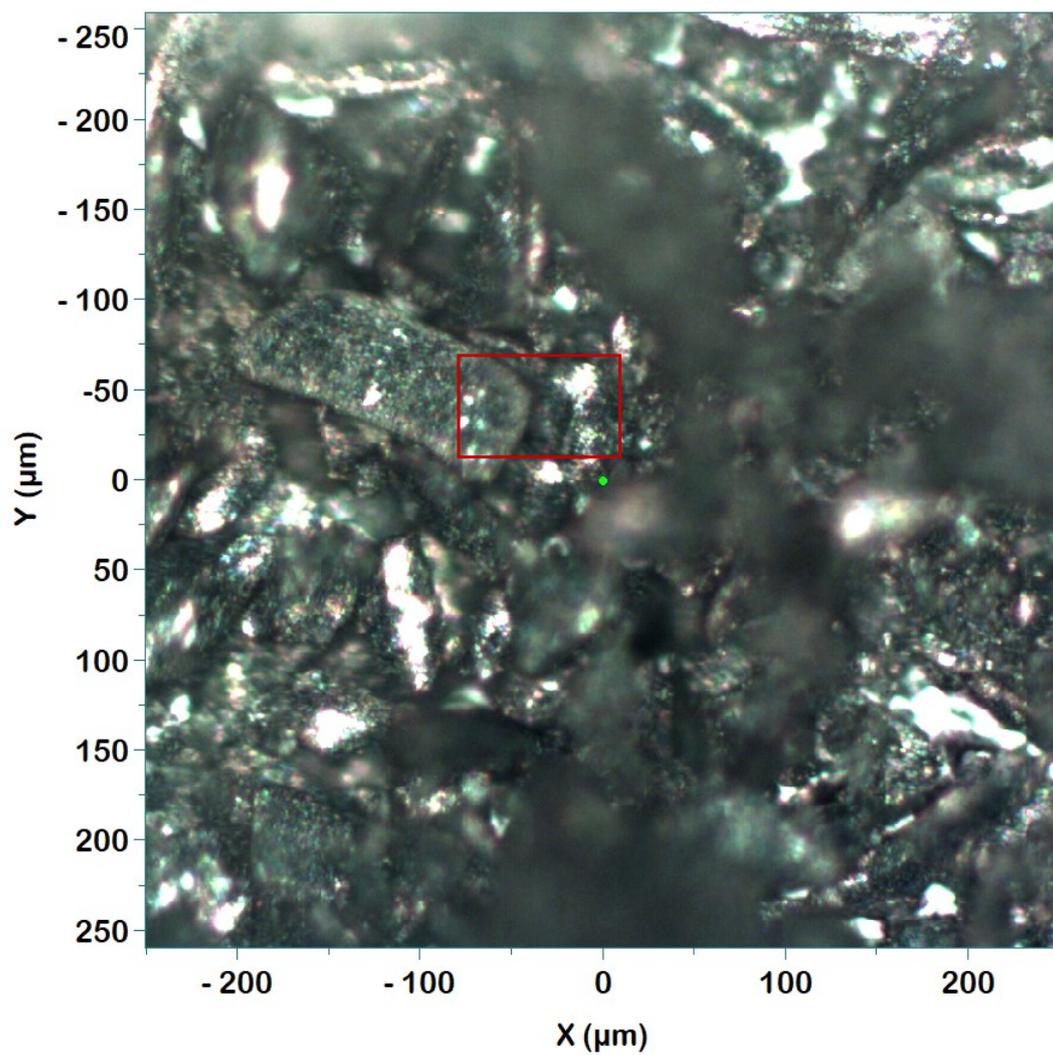
**Figure S7.** SEM images and corresponding EDS elemental mapping images of the (a) NPM and (b) PM- Zn<sub>0.30</sub> contact masses after reaction at 295 °C (89-92% of CH<sub>3</sub>Cl conversion, 0.5-0.6% of Si conversion).



**Figure S8.** Evolution with cumulative reaction time of C production and M2 production with contact mass PM-Zn0.30 tested after consecutive  $CH_3Cl$  injections.



**Figure S9.** Typical Raman spectrum (a) before and (b) after background subtraction of the PM-Zn<sub>0.30</sub> contact mass after reaction at X(Si) = 1.5%.



**Figure S10.** Optical image recorded using a 10x objective of the PM-Zn<sub>0.30</sub> contact mass after reaction at X(Si) = 13.9%. The Raman mapping area is outlined in red. The same area was analyzed by SEM and retrieved with Raman spectrometer using a Nano-GPS.

## References

- 1 D. D. Wagman, W. H. Evans, V. B. Parker, R. H. Schumm, I. Halow, S. M. Bailey, K. L. Churney and R. L. Nuttall, *Journal of Physical and Chemical Reference Data*.
- 2 CRC Handbook of Chemistry and Physics, 84th Edition Edited by David R. Lide (National Institute of Standards and Technology). *J. Am. Chem. Soc.* 2004, **126**, 1586–1586.
- 3 H. Schimpff, *Zeitschrift für Physikalische Chemie*, 1910, **71U**, 257–300.
- 4 R. R. Chromik, W. K. Neils and E. J. Cotts, *J. Appl. Phys.*, 1999, **86**, 4273–4281.
- 5 D. Lüdecke, *Calphad*, 1987, **11**, 135–142.
- 6 D. Shin, J. E. Saal and Z.-K. Liu, *Calphad*, 2008, **32**, 520–526.